

10/578529

IAP12 Rec'd PCT/PTO 03 MAY 2006

Express Mail" mailing label number: EV 316053070 USDate of Deposit: May 3, 2006

Case No. 9905/42

Client No. BIF116037/US

**UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:	)	
	)	
HITZ et al.	)	
	)	Examiner:
Serial No.: Not Yet Assigned	)	Not Yet Assigned
	)	
Filing Date: Herewith	)	Group Art Unit:
	)	Not Yet Assigned
For: DEVICE FOR CONTROLLING	)	
ELECTRON TEMPERATURE IN AN ECR	)	
PLASMA	)	

**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Dear Sir:

In accordance with the duty of disclosure under 37 C.F.R. §1.56 and §§1.97-1.98, and more particularly in accordance with 37 C.F.R. §1.97(b), Applicants hereby cite the following references:

**U.S. AND FOREIGN REFERENCES**

Patent/ Publication No.	Date of Issue/Publication	Patentee/Applicant/Country
5,350,974	09/27/1994	Jacquot
4,717,178	08/14/1981	Geller et al.
FR 2 681 186 A1	03/12/1993	France
FR 2 475 798 A1	02/13/1980	France

**OTHER ART**

Antoni et al., "Edge Plasma Investigation on the Reversed Field Pinch ETA BETA II," <i>Journal of Nuclear Materials</i> , 176 & 177 (1990), pp. 1076-1082.
Drentje, A. "Techniques to Improve Highly Charged Ions Output from ECRISs," 15th International Seminar on ECR ion sources, University of Jyväskylä, Finland, June 2002.

Gammino <i>et al.</i> "Operation of the SERSE Superconducting ECR Ion Source at 28 GHz," <i>Review of Scientific Instruments</i> , Vol. 72, No. 11, p. 4090, November 2001
Girard <i>et al.</i> "Electron Cyclotron Resonance Ion Sources: Experiments and Theory", 12th International Seminar on ECR ion sources, 25-27 April 1995, Riken, Japan, pp. 164-169.
Gotoh <i>et al.</i> , "Studies on Properties of Low-Z Ceramics as Limiter Materials – Electron Beam and Textor Limiter Tests," <i>Journal of Nuclear Materials</i> 133 & 134 (1985), pp. 257-262.
Maekawa <i>et al.</i> , "Heat Flux of Fast Electrons to the Limiter in Lower Hybrid Current Drive Plasma on WT-3," <i>Nuclear Fusion</i> , Vol. 32, No. 10 (1992), pp. 1755-1767.
McGuire <i>et al.</i> , "ELM Activity During Limiter H-modes on TFTR," <i>Journal of Nuclear Materials</i> , 176 & 177 (1990), pp. 711-715.
Shimada <i>et al.</i> , "Large Amplitude Oscillations of Soft X-Rays in a High Current Density Plasma on TPE-1RM15 Reversed Field Pinch," <i>Plasma Phys. Control. Fusion</i> 36 (1994), pp. 561-572.
Volkov <i>et al.</i> , "Analytical Study of the Scrape-Off Layer and the Plasma Column Periphery," I.V. Kurchatov Institute of Atomic Energy, Moscow, USSR, pp. 39-42.
Yang <i>et al.</i> , "Plasma Sources and Characterizations in the R.F. Test Facility," <i>Surface and Coatings Technology</i> 112 (1999), pp. 52-55.

For the Examiner's convenience, Applicants are enclosing Form PTO-1449 (one sheet) and copies of cited references A3-A14. Applicants respectfully request the Examiner's consideration of the above references and entry thereof into the record of this application.

In accordance with 37 C.F.R. §1.98(a)(3), the applicants state as follows:

FR 2 681 186 A1 discloses an electron cyclotron resonance (ECR) ion source. A non-certified English translation of the Abstract is enclosed herewith. Applicants have also cited the corresponding U.S. Patent No. 5,350,974 B1.

FR 2 475 798 A1 discloses a process for producing highly charged ions. A non-certified English translation of the Abstract is enclosed herewith. Applicants have also cited the corresponding U.S. Patent No. 4,417,178 B1

Also enclosed is a copy of the International Search Report dated October 10, 2005 for the corresponding PCT Application No. WO2005/046296 A3.

By submitting this Statement, Applicants are attempting to fully comply with the duty of candor and good faith mandated by 37 C.F.R. §1.56. As such, this

10/578529

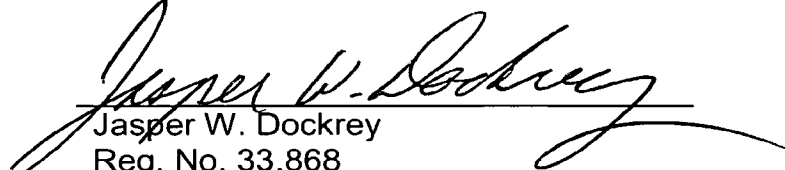
IAP12 Rec'd PCT/PTO 03 MAY 2006

Statement is not intended to constitute an admission that any of the enclosed references, or other information referred to therein, constitutes "prior art" or is otherwise "material to patentability," as that phrase is defined in 37 C.F.R. §1.56(a).

Applicants have calculated no fee to be due in connection with the filing of this Statement. However, the Director is authorized to charge any fee deficiency associated with the filing of this Statement to a deposit account, as authorized in the Transmittal accompanying this Statement.

Respectfully submitted,

May 3, 2006

  
Jasper W. Dockrey  
Reg. No. 33,868  
Attorney for Applicants

BRINKS HOFER GILSON & LIONE  
Post Office Box 10395  
Chicago, Illinois 60610  
312/321-4200

FORM PTO-1449	SERIAL NO. Not Yet Assigned	CASE NO. 9905/42 (BIF116037/US)
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	FILING DATE Herewith	GROUP ART UNIT Not Yet Assigned
APPLICANTS: HITZ et al.		

## REFERENCE DESIGNATION U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	NAME	CLASS/ SUBCLASS	FILING DATE
/R.D./	A1	5,350,974	09/27/1994	Jacquot		
/R.D./	A2	4,717,178	08/14/1981	Geller et al.		

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES OR NO
/R.D./	A3	FR 2 681 186 A1	03/12/1993	France		Abstract
/R.D./	A4	FR 2 475 798 A1	02/13/1980	France		Abstract

EXAMINER INITIAL	OTHER ART – NON-PATENT LITERATURE DOCUMENTS <small>(Include name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.)</small>					
/R.D./	A5	Antoni et al., "Edge Plasma Investigation on the Reversed Field Pinch ETA BETA II," <i>Journal of Nuclear Materials</i> , 176 & 177 (1990), pp. 1076-1082.				
	A6	Drentje, A. "Techniques to Improve Highly Charged Ions Output from ECRISs," 15th International Seminar on ECR ion sources, University of Jyväskylä, Finland, June 2002.				
	A7	Gammino et al. "Operation of the SERSE Superconducting ECR Ion Source at 28 GHz," <i>Review of Scientific Instruments</i> , Vol. 72, No. 11, p. 4090, November 2001				
	A8	Girard et al. "Electron Cyclotron Resonance Ion Sources: Experiments and Theory", 12th International Seminar on ECR ion sources, 25-27 April 1995, Riken, Japan, pp. 164-169.				
	A9	Gotoh et al., "Studies on Properties of Low-Z Ceramics as Limiter Materials – Electron Beam and Textor Limiter Tests," <i>Journal of Nuclear Materials</i> 133 & 134 (1985), pp. 257-262.				
	A10	Maekawa et al., "Heat Flux of Fast Electrons to the Limiter in Lower Hybrid Current Drive Plasma on WT-3," <i>Nuclear Fusion</i> , Vol. 32, No. 10 (1992), pp. 1755-1767.				
	A11	McGuire et al., "ELM Activity During Limiter H-modes on TFTR," <i>Journal of Nuclear Materials</i> , 176 & 177 (1990), pp. 711-715.				
	A12	Shimada et al., "Large Amplitude Oscillations of Soft X-Rays in a High Current Density Plasma on TPE-1RM15 Reversed Field Pinch," <i>Plasma Phys. Control. Fusion</i> 36 (1994), pp. 561-572.				
	A13	Volkov et al., "Analytical Study of the Scrape-Off Layer and the Plasma Column Periphery," I.V. Kurchatov Institute of Atomic Energy, Moscow, USSR, pp. 39-42.				
	A14	Yang et al., "Plasma Sources and Characterizations in the R.F. Test Facility," <i>Surface and Coatings Technology</i> 112 (1999), pp. 52-55.				

EXAMINER /Rakesh Dhingra/	DATE CONSIDERED 09/05/2010
------------------------------	-------------------------------

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.